

2/13/82  
PATENT

0171-0819P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: SHINGAGAWA, Tsutomu et al. Conf.:  
Appl. No.: New Group:  
Filed: February 13, 2002 Examiner:  
For: PHOTOMASK BLANK, PHOTOMASK AND METHOD OF  
MANUFACTURE

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents  
Washington, DC 20231

February 13, 2002

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE SPECIFICATION:

Please replace page 10 with the new page 10 attached hereto.